● PRINTER RUSH ● (PTO ASSISTANCE)

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NOTE: This form will be included as part of the official USPTO record, with the Response document coded as XRUSH.

REV 10/04

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- 10. (Currently Amended) A method for making a transistor device by laser synthesis directly onto a monolithic substrate of essentially of a crystalline or polycrystalline wide-bandgap semiconductor compound, said method comprising, the steps of:
- a. providing a monolithic wide-bandgap semiconductor compound substrate having a reverse side and of essentially n-type semiconductive carriers responsive to laser synthesis conversion;
- b. converting a first section of said substrate to a p-type semiconductive carrier by laser synthesis;
- c. converting a second section of said substrate to a p-type semiconductive carrier by laser synthesis spaced apart from said first p-type carrier section, to thereby form a separation therebetween;
- d. inscribing on said substrate by laser synthesis a first conductor connected to said first ptype section and a second conductor connected to said second p-type section, to provide electrical
 connections to said first and second p-type sections, respectively;
- e. inscribing on said reverse side of said substrate a third said p-type section sections on said substrate, and a third conductor, said third conductors providing means for connecting said device to other and external components, elements and circuits, and to thereby provide a p-n-p type semiconductor transistor.
- 11. (Original) A method for making a transistor device of claim 10, which includes the steps of placing said p-n-p transistor in a hermetically sealed chamber having a laser beam transmission window therein, and forming a first dielectric layer on a surface of said substrate disposed between said spaced apart p-type carrier sections and a second conductor layer on top of said dielectric layer by means of laser synthesis and various selected metallo-organic gases introduced into said chamber, and said laser